



Form PTO-1449 U.S. Department of Commerce Patent and Trademark Office  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Atty. Docket No.	Serial No.
	FSI0041/US/3	10/628,598
	Applicant	
	Daggett et al.	
	Filing Date	Group
	July 28, 2003	

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
Jc	4,932,353	06/1990	Kawata et al.			
	5,127,362	07/1992	Iwatsu et al.			
	5,211,753	05/1993	Swain			
	5,366,757	11/1994	Lin			
	5,416,047	05/1995	Konishi et al.			
	5,626,679	05/1997	Shimizu et al.			
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	6,177,133	01/2001	Gurer et al.			
	6,599,560	07/2003	Daggett et al.			

## FOREIGN PATENT DOCUMENTS

Name	Document Number	Date	Country	Class	Subclass	Translation Yes/No
Jc	3-178123	08/1991	Japan			Abstract
	4-94525	03/1992	Japan			Abstract
	05-144721	06/1993	Japan			Abstract

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Jc	Uchiyama, Photoresist Application Device, JP 5-144721 (English Translation), June 1993, pp. 1-10
	Gürer, et al. "Model-based adaptive process control: A CD-control example," Solid State Technology, pp. 205-206, 208, 210, 212 (July 1996)
	Gürer, et al., "...Adaptive Process Control in Lithography," Semicon Korea 98, Semicon Korea Technical Symposium 98, Process & Evaluation Technology I, II, pp. 205-218

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Ekr: Jc

Date Considered: 5/06